ABSTRACT OF THE DISCLOSURE

A thermal physical vapor deposition source for depositing material onto a substrate includes an elongated container for receiving the material, the container having a conductance C_B in the elongated direction, and a heater for heating the material in the container to vaporize the material to a partial pressure P_m. The container has at least one member defining a plurality of apertures arranged along the length of the member, the apertures having a total conductance C_A, wherein $\frac{C_A}{C_B} \leq 0.5$, and end heaters for heating each side of the container to reduce condensation of material onto the container.